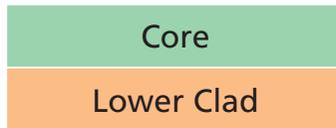


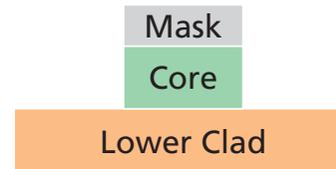
Formation of Clad & Core



Substrate (Si, Silica)

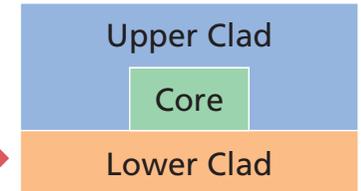
- Formation of Lower Clad & Core Layer → **PECVD CME-200**
- Thermal Treatment → **Annealer**

Core Layer Etching



- Mask Formation → **Sputter SME-200, Evaporation EBX-1000**
- Mask Etcher → **NE-5500**
- Resist Stripper → **ENVIRO**
- Etcher of Core Layer → **NLD-6000, NLD-800**

Formation of Upper Clad



- Covering of Core Layer → **PECVD CME-200**

Clad & Core Deposition



CME-200

Annealing



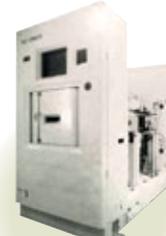
V6-100

Metal Mask Deposition



SME-200

Mask Etching



NE-5500

Resist Stripping



ENVIRO

Core Layer Etching



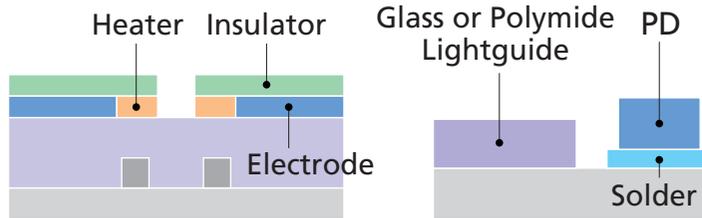
NLD-6000

Upper Clad Deposition



CME-200

Formation of Electrode, Solder & Heater



Sputtering System for Heat Film, Electrode Film Deposition



SV-4540

Evaporation System for Solder and Electrode Film Deposition



EBX-1000

ULVAC, Inc.

Standardized Equipment

PECVD



CME-200

Sputter



SME-200

Etcher



NLD-6000

ULVAC, Inc.

1. Cassette to Cassette type Equipment performed small footprint and low price.
2. $\phi 3\sim 8''$ substrate available (option; unknown size, square substrate)
3. Control System; GPCS (touch panel computer + sequencer) developed by ULVAC
4. Standardization of cassette chamber, transfer chamber and transfer robot etc. in each equipment